NOIDA INSTITUTE OF ENGG. & TECHNOLOGY, GREATER NOIDA, GAUTAM BUDDH NAGAR (AN AUTONOMOUS INSTITUTE)



Affiliated to

DR. A.P.J. ABDUL KALAM TECHNICAL UNIVERSITY UTTAR PRADESH, LUCKNOW



Evaluation Scheme & Syllabus

For

Master of Technology VLSI Design First Year

(Effective from the Session: 2022-23)

NOIDA INSTITUTE OF ENGG. & TECHNOLOGY, GREATER NOIDA, GAUTAM BUDDH NAGAR (AN AUTONOMOUS INSTITUTE)

Master of Technology VLSI Design EVALUATION SCHEME SEMESTER-I

SI.	Subject	Subject	P	eriod	ls	E	valuat	ion Schemes	5		End Semester		Credit
No.	Codes		L	Т	Р	СТ	ТА	TOTAL	PS	TE	PE		
1	AMTVL0101	CMOS Digital VLSI Design	3	0	0	20	10	30		70		100	3
2	AMTVL0102	Advanced Digital Design using Verilog	3	0	0	20	10	30		70		100	3
3	AMTCC0101	Research Process and Methodology	3	0	0	20	10	30		70		100	3
5		Departmental Elective-I	3	0	0	20	10	30		70		100	3
6		Departmental Elective-II	3	0	0	20	10	30		70		100	3
7	AMTVL0151	CMOS Digital VLSI Design Lab	0	0	4				20		30	50	2
8	AMTVL0152	Advanced Digital Design Lab using Verilog	0	0	4				20		30	50	2
		TOTAL										600	19

Departmental Elective-I:

- 1. AMTVL0111 Microelectronics
- 2. AMTVL0112 MOS Device Modeling
- 3. AMTVL0113 Analog IC Design

Departmental Elective-II:

- 1. AMTVL0114 Microchip Fabrication Technology
- 2. AMTVL0115 Clean Room Technology and Maintenance
- 3. AMTVL0116 ULSI Technology

Abbreviation Used:-

L: Lecture, T: Tutorial, P: Practical, CT: Class Test, TA: Teacher Assessment, PS: Practical Sessional, TE: Theory End Semester Exam., PE: Practical End Semester Exam.

NOIDA INSTITUTE OF ENGG. & TECHNOLOGY, GREATER NOIDA, GAUTAM BUDDH NAGAR (AN AUTONOMOUS INSTITUTE)

Master of Technology VLSI Design EVALUATION SCHEME SEMESTER-II

SI.	Subject	Subject	Р	erio	ls]	Evalua	tion Scheme	S	End Semester		Total	Credit
No	Codes		L	T	Р	СТ	TA	TOTAL	PS	ТЕ	PE		
1	AMTVL0201	Digital Design Using FPGA and CPLD	3	0	0	20	10	30		70		100	3
2	AMTVL0202	Low Power VLSI Design	3	0	0	20	10	30		70		100	3
3		Departmental Elective-III	3	0	0	20	10	30		70		100	3
4		Departmental Elective-IV	3	0	0	20	10	30		70		100	3
5		Departmental Elective-V	3	0	0	20	10	30		70		100	3
6	AMTVL0251	Digital Design Using FPGA and CPLD Lab	0	0	4				20		30	50	2
7	AMTVL0252	Low Power VLSI Design Lab	0	0	4				20		30	50	2
8	AMTVL0253	Seminar-I	0	0	2				50			50	1
		TOTAL										650	20

Departmental Elective-III:

- 1. AMTVL0211 VLSI Testing and Testability
- 2. AMTVL0212 VLSI DSP Architectures
- 3. AMTVL0213 Full Custom Design

Departmental Elective-IV:

- 1. AMTVL0214 MEMS Sensor Design
- 2. AMTVL0215 Nanoscale Devices: Modeling & Simulation
- 3. AMTVL0216 Physical Design & Automation

Departmental Elective-V:

- 1. AMTVL0217 Embedded Microcontrollers
- 2. AMTVL0218 Real Time Operating System
- 3. AMTVL0219 SOC Design using ARM

Abbreviation Used:-

L: Lecture, T: Tutorial, P: Practical, CT: Class Test, TA: Teacher Assessment, PS: Practical Sessional, TE: Theory End Semester Exam., PE: Practical End Semester Exam.

	AMTVL0101	LTP	Credit
Course Title	CMOS Digital VLSI Design	300	03
Course Objec	tive:	I	1
1	To explain basics of MOS switch, MOS fabrication and		
	their characteristics.		
2	To explain basic concept of CMOS inverter operation, its		
	characteristics and switching power dissipation.		
3	To design static CMOS combinational and sequential		
	logic at the transistor level, including mask layout.		
4 5	To explain the concept of dynamic logic circuits.		
3	To design functional units including ROMs, SRAMs, and DRAM.		
Pro_requisites	: Basics of CMOS.		
1 I C-I Equisites	Course Contents / Syllabus		
UNIT-I	MOS TRANSISTOR BASIC	101	nours
	Basic, MOS switch, VLSI Design flow & Y-Chart, Basic cond order effect, Fabrication Process Flow: Basic Steps,		•
1	Design Rules, MOS inverters: DC transfer characteristics.		
capacitances.	Design Rules, WOS inverters. De transfer enaracteristics	, iatenup,	MOSPET
UNIT-II	CMOS INVERTER		9hours
	Circuit operation, DC transfer characteristics, noise margin:	calculati	
	in of CMOS inverter, Supply voltage scaling, power and		
	eteristic: Delay time definition, calculation of delay times,		
_	Switching Power dissipation of CMOS inverter.		e
,			
UNIT-III	COMBINATIONAL & SEQUENTIAL MOS LOGIC		8hours
UNIT-III	CIRCUITS		8hours
UNIT-III Combinational M	CIRCUITS IOS Logic Circuits: MOS logic circuits with NMOS loa		olex Logic
UNIT-III Combinational M circuits design –	CIRCUITS MOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM	IOS gates	olex Logic , AOI and
UNIT-III Combinational M circuits design –	CIRCUITS IOS Logic Circuits: MOS logic circuits with NMOS loa	IOS gates	olex Logic , AOI and
UNIT-III Combinational M circuits design – OIA gates, CMO	CIRCUITS MOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans	IOS gates smission g	olex Logic , AOI and gates,
UNIT-III Combinational M circuits design – OIA gates, CMO Sequential MOS	CIRCUITS MOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans Logic Circuits: Behavior of bi-stable elements, D latch, SR I	IOS gates smission g	olex Logic , AOI and gates,
UNIT-III Combinational M circuits design – OIA gates, CMO Sequential MOS and flip flop circu	CIRCUITS MOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans Logic Circuits: Behavior of bi-stable elements, D latch, SR I hits, CMOS, and edge triggered flip-flop.	IOS gates smission g	olex Logic , AOI and gates, ocked latch
UNIT-III Combinational M circuits design – OIA gates, CMO Sequential MOS and flip flop circu UNIT-IV	CIRCUITS IOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans Logic Circuits: Behavior of bi-stable elements, D latch, SR I uits, CMOS, and edge triggered flip-flop. DYNAMIC LOGIC CIRCUITS	1OS gates smission g Latch, Clo	olex Logic , AOI and gates, ocked latch 9hours
UNIT-III Combinational M circuits design – OIA gates, CMO Sequential MOS and flip flop circu UNIT-IV Logic Circuits: H	CIRCUITS IOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans Logic Circuits: Behavior of bi-stable elements, D latch, SR I hits, CMOS, and edge triggered flip-flop. DYNAMIC LOGIC CIRCUITS Basic principle of pass transistor circuits, Voltage Bootstra	IOS gates smission g Latch, Clo pping, Sy	olex Logic , AOI and gates, ocked latch 9hours mchronous
UNIT-III Combinational M circuits design – OIA gates, CMO Sequential MOS and flip flop circu UNIT-IV Logic Circuits: H	CIRCUITS IOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans Logic Circuits: Behavior of bi-stable elements, D latch, SR I uits, CMOS, and edge triggered flip-flop. DYNAMIC LOGIC CIRCUITS	IOS gates smission g Latch, Clo pping, Sy	olex Logic , AOI and gates, ocked latch 9hours mchronous
UNIT-III Combinational M circuits design – OIA gates, CMO Sequential MOS and flip flop circu UNIT-IV Logic Circuits: I dynamic circuit t CMOS	CIRCUITS IOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans Logic Circuits: Behavior of bi-stable elements, D latch, SR I hits, CMOS, and edge triggered flip-flop. DYNAMIC LOGIC CIRCUITS Basic principle of pass transistor circuits, Voltage Bootstra	IOS gates smission g Latch, Clo pping, Sy	olex Logic , AOI and gates, ocked latch 9hours mchronous e Dynamic
UNIT-III Combinational M circuits design – OIA gates, CMO Sequential MOS and flip flop circu UNIT-IV Logic Circuits: H dynamic circuit t CMOS UNIT-V	CIRCUITS IOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans Logic Circuits: Behavior of bi-stable elements, D latch, SR I uits, CMOS, and edge triggered flip-flop. DYNAMIC LOGIC CIRCUITS Basic principle of pass transistor circuits, Voltage Bootstra echniques, Dynamic CMOS transmission gate logic, High per SEMICONDUCTOR MEMORIES	1OS gates smission g Latch, Clo pping, Sy erformanc	olex Logic a, AOI and gates, ocked latch 9hours mchronous e Dynamic 8 hours
UNIT-III Combinational M circuits design – OIA gates, CMO Sequential MOS and flip flop circu UNIT-IV Logic Circuits: H dynamic circuit t CMOS UNIT-V Semiconductor M	CIRCUITS MOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans Logic Circuits: Behavior of bi-stable elements, D latch, SR I aits, CMOS, and edge triggered flip-flop. DYNAMIC LOGIC CIRCUITS Basic principle of pass transistor circuits, Voltage Bootstra echniques, Dynamic CMOS transmission gate logic, High pe SEMICONDUCTOR MEMORIES femories: Types, RAM array organization, DRAM – Types,	IOS gates smission g Latch, Clo pping, Sy erformanc	olex Logic , AOI and ates, ocked latch 9hours mchronous e Dynamic 8 hours n, Leakage
UNIT-III Combinational M circuits design – OIA gates, CMO Sequential MOS and flip flop circu UNIT-IV Logic Circuits: H dynamic circuit t CMOS UNIT-V Semiconductor M currents in DRAI	CIRCUITS IOS Logic Circuits: MOS logic circuits with NMOS loa Realizing Boolean expressions using NMOS gates and CM S full adder, CMOS transmission gates, Designing with Trans Logic Circuits: Behavior of bi-stable elements, D latch, SR I uits, CMOS, and edge triggered flip-flop. DYNAMIC LOGIC CIRCUITS Basic principle of pass transistor circuits, Voltage Bootstra echniques, Dynamic CMOS transmission gate logic, High per SEMICONDUCTOR MEMORIES	IOS gates smission g Latch, Clo pping, Sy erformanc	olex Logic , AOI and gates, ocked latch 9hours mchronous e Dynamic 8 hours n, Leakage

CO 1	To identify the fabrication process of CMOS transistor.
CO 2	To identify basic concept of CMOS inverter operation, its
	characteristics and switching power dissipation.
CO 3	Design combinational & Sequential MOS logic circuits
	like latches and flip flops.
CO 4	Explain and design synchronous dynamic pass transistor
	circuits
CO 5	Analyse SRAM cell and memory arrays.

Text Books

1. Sung-Mo Kang & Yusuf Leblebici, CMOS Digital Integrated Circuits - Analysis & Design, , MGH, Third Ed., 2003

2. Jan M Rabaey, Digital Integrated Circuits - A Design Perspective, Prentice Hall, Second Edition, 2005

3. David A. Hodges, Horace G. Jackson, and Resve A. Saleh, Analysis and Design of Digital Integrated Circuits, Third Edition, McGraw-Hill, 2004

Reference Books

1. R. J. Baker, H. W. Li, and D. E. Boyce, CMOS circuit design, layout, and simulation, Wiley-IEEE Press, 2007

2. Christopher Saint and Judy Saint, IC layout basics: A practical guide, McGraw-Hill Professional, 2001

	M. TECH FIRST YEAR					
Course Code	AMTVL0102	LTP	Credit			
Course Title	Advanced Digital Design using Verilog	300	03			
Course Object						
<u>1</u>	Study and explain the basic concepts Verilog HDL	/•				
2	Implement digital circuits using distinct design styl					
3	Design and synthesis digital circuits using HDLs.					
4						
5	Ŭ					
Pre-requisites:	Digital System Design					
4	Course Contents / Syllabus					
UNIT-I	INTRODUCTION TO HARDWARE DESCH	RIPTION	8 hours			
	LANGUAGE (HDL)		0 nours			
(HDL), Verilog Doperators, Data ty	esign Process, Hardware modeling, Introduction to anguage features, elements of Verilog, Top-Dow pes in Verilog; net type, reg type, wire type, Verilo delays and simulation, inertial delay effects and pul	n, Bottom og Models	-up Design, Verilog of propagation delay			
UNIT-II	DISTINCT DESIGN STYLES	j	8 hours			
flow level, proce	n styles, behavioral and structural design style, Ver dural assignment, blocking / non-blocking assignr , writing Verilog test benches.					
UNIT-III	SYNTHESIS OF COMBINATIONAL & SEQUENTIAL LOGIC		8 hours			
	esis - technology-independent design, styles for s synthesis of finite state machines, synthesis of gate ures.					
UNIT-IV	DATA PATH AND CONTROLLER DESIGN		8 hours			
Modeling finite state machines, Data-path and Controller Design, Synthesizable Verilog, Modeling memory, Modeling register banks, Switch level modeling.						
UNIT-V	PIPELINING AND PROCESSOR DESIGN		8 hours			
Basic pipelining modeling of the p	concepts, Pipeline modeling, Pipeline implement rocessor.	tation of a	a processor, Verilog			
Course Outcon to	me: After successful completion of this co	urse stu	dents will be able			
CO 1	Outline the basic concepts Verilog HDL.					
CO 2	Design of digital circuits using distinct design style	es.				
CO 3	Model HDL based Synthesis of digital circuits.					
CO 4	Analyze the concepts of data path design and switc modeling.	ch level				

CO 5	Implement pipelining and processor design using Verilog
	modeling.
Text books	
1. Navabi, Z., 199	9. Verilog digital system design. McGraw-Hill.
2. Palnitkar, S., 20	03. Verilog HDL: a guide to digital design and synthesis (Vol. 1). Prentice Hall
Professional.	
3. Arnold, M.G., 1	998. Verilog digital computer design: Algorithms into hardware. Prentice-Hall,
Inc.	
Reference Boo	ks
1. Lin, M.B., 2008	B. Digital system designs and practices: using Verilog HDL and FPGAs. Wiley
Publishing.	
2. Unsalan, C. and	Tar, B., 2017. Digital system design with FPGA: implementation using Verilog
and VHDL. McGr	aw-H

Link:	
Unit 1	https://www.youtube.com/watch?v=wiNDn19GpRU&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=3
Unit 2	https://www.youtube.com/watch?v=xWimKdisUXE&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=12
Unit 3	https://www.youtube.com/watch?v=lpS3S2gVoB4&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=23
Unit 4	https://www.youtube.com/watch?v=cIDoJtYdDVA&t=66s
Unit 5	https://www.youtube.com/watch?v=w1u338oIeTQ

Course Code	AMTCC0101	LTP	Credit		
Course Title	Research Process & Methodology	3 0 0	03		
Course Obje	rtive:				
<u>v</u>	o explain the concept / fundamentals of research and the	neir types			
	o study the methods of research design and steps of rese				
	o explain the methods of data collection and proceed chniques	dure of sampling			
4 To analyze the data, apply the statistical techniques and understand the concept of hypothesis testing					
	o study the types of research report and technical writin	ng.			
	s: Basics of Statistics	-			
•	Course Contents / Syllabus				
UNIT-I	INTRODUCTION TO RESEARCH		8 hours		
Analytical, App	ctive and motivation of research, types and approache blied vs. Fundamental, Quantitative vs. Qualitative				
	ds versus Methodology, significance of research, criter		h.		
UNIT-II Research proces objective of Lite	ds versus Methodology, significance of research, criter RESEARCH FORMULATION AND DESIGN is and steps involved, Definition and necessity of rese erature review, Locating relevant literature, Reliability	ia of good researc arch problem. Im of a source, Wri	h. 8 hours portance and ting a survey		
UNIT-II Research proces objective of Lite and identifying design.	ds versus Methodology, significance of research, criter RESEARCH FORMULATION AND DESIGN as and steps involved, Definition and necessity of rese erature review, Locating relevant literature, Reliability the research problem, Literature Survey, Research I	ia of good researc arch problem. Im of a source, Wri	h. 8 hours portance and ting a survey of research		
UNIT-II Research proces objective of Lite and identifying design. UNIT-III	ds versus Methodology, significance of research, criter RESEARCH FORMULATION AND DESIGN as and steps involved, Definition and necessity of rese erature review, Locating relevant literature, Reliability the research problem, Literature Survey, Research I DATA COLLECTION	ia of good researc arch problem. Im of a source, Wri Design, Methods	h. 8 hours portance and ting a survey of research 8 hours		
UNIT-II Research process objective of Lite and identifying design. UNIT-III Classification o primary and sec	ds versus Methodology, significance of research, criter RESEARCH FORMULATION AND DESIGN as and steps involved, Definition and necessity of rese erature review, Locating relevant literature, Reliability the research problem, Literature Survey, Research I	ia of good researce arch problem. Im of a source, Wri Design , Methods Data Collection, G neory and Technic	h. 8 hours portance and ting a survey of research 8 hours Collection of		
UNIT-II Research process objective of Lite and identifying design. UNIT-III Classification o primary and sec	ds versus Methodology, significance of research, criter RESEARCH FORMULATION AND DESIGN is and steps involved, Definition and necessity of rese erature review, Locating relevant literature, Reliability the research problem, Literature Survey, Research I DATA COLLECTION f Data, accepts of method validation, Methods of I ondary data, sampling, need of sampling, sampling th	ia of good researce arch problem. Im of a source, Wri Design , Methods Data Collection, G neory and Technic	h. 8 hours portance and ting a survey of research 8 hours Collection of jues, steps in		
UNIT-II Research process objective of Lite and identifying design. UNIT-III Classification o primary and sec sampling design UNIT-IV Processing Ope appropriate stat statistical infere Visualization – 1	ds versus Methodology, significance of research, criter RESEARCH FORMULATION AND DESIGN s and steps involved, Definition and necessity of rese erature review, Locating relevant literature, Reliability the research problem, Literature Survey, Research I DATA COLLECTION f Data, accepts of method validation, Methods of I ondary data, sampling, need of sampling, sampling th different types of sample designs, ethical consideration DATA ANALYSIS rations, Data analysis, Types of analysis, Statistical istical technique, Hypothesis Testing, Data processing ence, Chi-Square Test, Analysis of variance(ANG Monitoring Research Experiments ,hands-on with LaTe	ia of good researce arch problem. Im of a source, Wri Design , Methods Data Collection, One ons in research. I techniques and ng software (e.g. DVA) and cova eX.	h. 8 hours portance and ing a survey of research 8 hours Collection of ues, steps in 8 hours choosing an SPSS etc.) riance, Data		
UNIT-II Research process objective of Lite and identifying design. UNIT-III Classification o primary and sec sampling design UNIT-IV Processing Ope appropriate stat statistical infere Visualization – I UNIT-V	ds versus Methodology, significance of research, criter RESEARCH FORMULATION AND DESIGN as and steps involved, Definition and necessity of rese erature review, Locating relevant literature, Reliability the research problem, Literature Survey, Research I DATA COLLECTION f Data, accepts of method validation, Methods of I ondary data, sampling, need of sampling, sampling th , different types of sample designs, ethical consideration DATA ANALYSIS rations, Data analysis, Types of analysis, Statistical istical technique, Hypothesis Testing, Data processing ence, Chi-Square Test, Analysis of variance(ANC	ia of good researce arch problem. Im of a source, Wri Design , Methods Data Collection, G aeory and Technic ons in research. I techniques and ng software (e.g. DVA) and cova eX. F RESEARCH	h. 8 hours portance and ting a survey of research 8 hours Collection of pues, steps in 8 hours choosing ar SPSS etc.) riance, Data 8 hours		

CO 1	Explain concept / fundamentals for different types of research				
CO 2	Apply relevant research Design technique				
CO 3	Use appropriate Data Collection technique				
CO 4	Evaluate statistical analysis which includes various parametric test and non-parametric test and ANOVA technique				
CO 5	Prepare research report and Publish ethically.				
Text books					
	 C. R. Kothari, Gaurav Garg, Research Methodology Methods and Techniques , New Age International publishers, Third Edition. 				
 Ranjit Kumar, Research Methodology: A Step-by-Step Guide for Beginners, 2nd Edition, SAGE 2005. 					
3. Deepak C	Chawla, NeenaSondhi, Research Methodology, Vikas Publication				
Reference Bo	ooks				

1. Donald Cooper & Pamela Schindler, Business Research Methods, TMGH, 9th edition

2. Creswell, John W. ,Research design: Qualitative, quantitative, and mixed methods approaches sage publications,2013

NPTEL/ You tube/ Faculty Video Link:

https://www.youtube.com/playlist?list=PL6G1C6j0WUTXqXL9O0CgTXCr1hL8HR2dY https://www.youtube.com/playlist?list=PLVok63jpnHrFFQI6BqkIksVqDnYG0ZI41 https://www.youtube.com/playlist?list=PLnbm2MNkZYwOVVedGBQtID-jKgj9dD8kW https://www.youtube.com/playlist?list=PLPjSqITyvDeWBBaFUbkLDJ0egyEYuNeR1 https://www.youtube.com/playlist?list=PLdj5pVg1kHiOypKNUmO0NKOfvoIThAv4N

		M. TECH FIRST YEAR		
Course C	Code	AMTVL0151	LTP	Credit
Course T	itle	CMOS Digital VLSI Design Lab	0 0 4	02
		List of Experiment		
Sr. No.	Nan	ne of Experiment		
1	Stud	y of Microwind software and its features.		
2		gn, simulate and verify the stick diagram of CMOS Inverter usi		vind.
3		gn, simulate and verify the result of universal gates using Micro VAND (b) NOR	owind	
4				
5	Y=((gn, simulate and verify the operation of logic functio $(B+CD)(E+F)$)'	_	
6		gn, simulate and verify the operation of CMOS half adder using		
7		gn, simulate and verify the operation of CMOS full adder usin owind.	ng two hal	f adders in
8	Desig	gn, simulate and verify the operation of 4:1 Multiplexer in Micr	owind.	
9	Desi	gn, simulate and verify the operation of logic function using I	Dynamic a	nd Domino
		in Microwind: Y=((<i>B</i>+C<i>D</i>)(<i>E</i>+F))'		
10	Desig	gn, simulate and verify pseudo NMOS Inverter.		
Lab Cou	irse O	utcome: After completion of this course students will be a	ble to	
CO 1		yze the features of Microwind software.		
CO 2		gn, simulate and verify the result of universal gates, XOR, XN		
CO 3		gn, simulate and verify the operation of logic function using Mi		
CO 4		gn, simulate and verify the operation of CMOS half/full adder u		owind.
CO 5	Desig	gn, simulate and verify the operation of Multiplexer in Microwit	nd.	
Link:				
		utube.com/watch?v=F-8_caipPsY		
-	•	ube.com/watch?v=S1VOEqApQvA		
		ube.com/watch?v=EHUJda2ttU8		
-	•	ibe.com/watch?v=yHJmFuexWbM		
https://www	w.youti	ube.com/watch?v=7K_0I6CjBOY		

	M. TECH FIRST YEAR				
Course Code	AMTVL0152	LTP	Credit		
Course Title	Advanced Digital Design Lab using Verilog	0 0 4	02		
0	d Functional Simulation of the following digital circuit elSim tools) using Verilog Hardware Description Lang		inx/		
Sr. No.	Name of Experiment				
1	Design and simulate the Verilog HDL code to describe	the function	ns of a Full		
	Adder and Subtractor using three modeling styles.				
2	Design and simulate the Verilog HDL code for the fo	ollowing			
	combinational circuits:				
	a) 4x1 Multiplexer using gate level modeling	1			
	b) 8x1 Multiplexer using dataflow level mode				
	c) 4-Bit Binary to Gray Code Converter using modeling	structural			
3	Design and simulate the Verilog HDL code for the follo	wing com	vinational		
	circuit:	wing com	mational		
	a) 3 to 8 Decoder				
	b) 8 to 3 Encoder				
4	Design and simulate the Verilog HDL code	for the	following		
	combinational circuits using structural modeling.		8		
	a) 16x1 Multiplexer using 4x1 Mux				
	b) 4- Bit Comparator using 1 Bit Comparato	r			
5	Design and simulate the Verilog HDL code for the b		netic and		
	bitwise logical operations of ALU.				
6	Design and simulate the Verilog HDL code for the flip-	-flops:			
	a) SR FF				
	b) JK FF				
	c) D FF				
	d) T FF				
7	Design and simulate the Verilog HDL code for the follo	owing cour	nters:		
	a) 4- Bit Up-Down Counter	1			
8	b) BCD counter (Synchronous reset and asyn				
0	Design and simulate the Verilog HDL code for the f	ollowing 2	- Bit Shili		
	register: a) SISO				
	a) SISO b) SIPO				
	c) PIPO				
	d) PISO				
9	Design and simulate the Verilog HDL code for 4- Bit un	iversal shi	ft register.		
10	Design and simulate the Verilog HDL code to detect the		-		
Lab Course	Outcome: After completion of this course students an				
CO 1	Translate the digital design into the Verilog HDL.				
CO 2	Design the combinational circuits in Verilog HDL.				
CO 3	Design the sequential circuits in Verilog HDL.				

CO 4	Implement different digital circuits with component testing.
Link:	
Unit 1	https://www.youtube.com/watch?v=wiNDn19GpRU&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=3
Unit 2	https://www.youtube.com/watch?v=xWimKdisUXE&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=12
Unit 3	https://www.youtube.com/watch?v=lpS3S2gVoB4&list=PLUtfVcb-iqn- EkuBs3arreilxa2UKIChl&index=23
Unit 4	https://www.youtube.com/watch?v=cIDoJtYdDVA&t=66s
Unit 5	https://www.youtube.com/watch?v=w1u338oIeTQ

		M. TECH FIRST YEAR		
Course C	Code	AMTVL0111	LTP	Credit
Course T	itle	Microelectronics	300	03
Course C	bject	tive:		8
1	0	ovide the knowledge of different fabrication proc	esses like	
	epitax	y, oxidation and their applications.		
2	-	ovide the knowledge of diffusion, ion implantation and	different	
		of lithography and etching.		
3		ovide the knowledge of Discrete devices and its fabricat		
4		ovide the knowledge of Different digital logic circuits a	nd analog	
5	circuit		-1	
		ovide the basic knowledge of BiCMOS ICs and their pa	ckaging.	
Pre-requ	isites	Basics of digital electronics, CMOS designing.		
		Course Contents / Syllabus		
UNIT-I		FABRICATION PROCESS		ours
	-	axy, Vapour phase epitaxy, Liquid phase epitaxy a	nd Molec	ular-Beam
		n on insulators.	. • • • •	N 1 111
		Polysilicon Film Deposition: Thermal oxidation, Dieleo	ctric and I	olysilicon
	lon, M	etallization & it's Application, Masking. DIFFUSION & ION IMPLANTATION		0.1
UNIT-II	· cc ·		1	8 hours
		n, Distribution and range of implanted ions, Annealin	ng and ac	tivation of
dopants		HY & ETCHING: Optical lithography, X-ray lithograp	hy Ion li	thooraphy
		lithography, Wet chemical etching and Dry chemical et		ulography,
UNIT-II		DISCRETE DEVICE FABRICATION		8 hours
	_	f p-n junction, Bipolar junction transistor, JFET,	MOSEE	
		-well, N-well & Twin top Process)	MODIL	I, EMOS
UNIT-IV	T	DESIGNING OF ANALOG AND DIGITAL CIRCUITS		8 hours
		for analog and digital ICs, functional elements availab		
	•	Circuits- Inverter, Two Input NOR Gate, Two Input NA	AND Gate	
Analog	circuit	s– single stage CE Amplifier and Emitter Follower.		
UNIT-V		BICMOS ICs		8 hours
Design	rules a	and Scaling, BICMOS ICs: Choice of transistor type	s, pnp tra	nsistors,
	· .	pacitors, Packaging: Chip characteristics, package fu	unctions,	package
operatio	ons.			
Course C	Jutco	me: After successful completion of this course stud	ents will	be able to
CO 1		Identify different fabrication processes		
CO 2		Implement diffusion, ion implantation and different		

	types of lithography and etching.
CO 3	Explain Discrete devices and their fabrication.
CO 4	Design different digital logic circuits and analogcircuits
CO 5	Categorize BiCMOS ICs and their packaging.
Text books	
1. Peter Va	n Zant, Microchip fabrication, McGraw Hill, 1997.
2. S.M. Sze	e, VLSI technology, McGraw-Hill Book company, NY, 1988.
Reference Bo	ooks
1. S.K. Gandh	i, 'VLSI Fabrication Principles'.
2. S.M. Sze, 'S	Semiconductor Devices Physics and Technology'.
3. Puckness D	ouglas A, Eshraghiaw Kamran "Basic VLSI Design" – Prentice Hall (India)
4. K.R. Botkar	; 'Integrated Circuits'

		M. TECH FIRST YEAR			
Course	Code	AMTVL0112	LTP	Credit	
Course	Title	MOS Device Modeling	300	03	
Course	Obiec	tive:	1		
1	V	dy and analysis of MOS structure, its operations a	and , MC	OS as a	
	capacit		,		
2	To stud	ly and analysis of MOSFET Device Characteristics.			
3		ly and analysis of Mobility models, MOS Performance	e parame	ters and	
	its freq	uency limitations.			
4		ly and analysis of SOI MOSFET.			
5		ly and analysis of SPICE Models for Semiconductor D	evices.		
Pre-req	uisites	Basic Electronics Engineering			
		Course Contents / Syllabus	1		
UNIT-I	-	MOS PHYSICS		8 hours	
Semicono	luctor su	rfaces, Ideal MOS structure, MOS device in thermal e	quilibriun	n, Non-Ideal	MOS:
work fun	ction di	fferences, charges in oxide, interface states, band diag	ram of no	n-ideal MO	S, flat-
band volt	age, ele	ctrostatics of a MOS (charge based calculations), calcu	lating vari	ous charges	across
the MOS	C, thres	hold voltage, MOS as a capacitor (2 terminal device),	Three ter	minal MOS	, effect
on thresh	old volta	age.			
UNIT-I	I	MOSFET DEVICE CHARACTERISTICS		8	hours
Field-Eff	ect Tran	sistors: MOSFET- basic operation and fabrication; th	reshold vo	oltages; outp	out and
transfer o	character	ristics of MOSFET, short channel and Narrow width	n effects,	MOSFET s	caling,
Small sig	nal mod	leling for low frequency and High frequency, high-k g	ate dielec	trics, ultra-s	hallow
junctions	, source	and drain resistance.			
UNIT-I	II	MOBILITY MODELS AND MOS		10) hours
		PERFORMANCE PARAMETERS			
		y, high field mobility, mobility various models, on cur			
		threshold swing, effect of interface states on sub threshol			
		effect of source bias and body bias on threshold voltage an	d device of	peration, Lar	ge signal
Ę,		gnal model for low, medium and high frequencies.	1		
UNIT-I	•	THE SOI MOSFET			hours
	•	MOSFETs: double gate, FINFET, comparison of capacitan			
		hort channel effects, current-voltage characteristics: Lim &			
·		and high field effects: Kink effect and Hot-carrier degradat	tion, Floati	ng body and	parasitic
BJT effect			1		
UNIT-V		SPICE MODELS FOR SEMICONDUCTOR DEVICES		8	hours
SPICE M		r Semiconductor Devices: MOSFET Level 1, Level 2 a	nd level 3	model, Mo	del
		,	-	, -	
parameter	rs;				
parameter Course		me: After successful completion of this course stud	ents will l	be able to	
*	Outco	me: After successful completion of this course stud ain and analyse MOS structure, its operations and , MO			

CO 3	Explain and analyse the Mobility models, MOS Performance parameters and its frequency limitations.
CO 4	Explain and analyse SOI MOSFET.
CO 5	Explain and analyse SPICE Models for Semiconductor Devices.
Fext Bo	oks
	H. Nicollian, J. R. Brews, Metal Oxide Semiconductor - Physics and Technology, Johiley and Sons.
Те	ndita Das Guptha, Amitava Das Guptha, Semiconductor Devices Modeling an chnology, Prentice Hall India
	an- PierrieColinge, Silicon-on-insulator Technology: Materials to VLSI, Kluwer Academ blishers group.
Referen	ce Books
1. P.	Colinge, "FinFETs and Other Multi-Gate Transistors", Springer. 2009
	nnis Tsividis, Operation and Modeling of the MOS transistor, Oxford University Press.
	Lecture Links:
Unit I:	
	www.youtube.com/watch?v=KohWxkovp0k
	www.youtube.com/watch?v=CT6olzelSKQ
https://	ocw.tudelft.nl/course-lectures/semiconductor-junction/
Unit II	:
https://	www.youtube.com/watch?v=0C4uxtS-tlQ
	www.youtube.com/watch?v=XcDeh98ppXk
	www.youtube.com/watch?v=uHTyw4GGnRo
	www.youtube.com/watch?v=xSh9PZZPpOc
Unit II	
	www.youtube.com/watch?v=4m49vM0Ryt8
-	www.youtube.com/watch?v=xgYdLvWcvms
	www.youtube.com/watch?v=IrbGAgrcvic
Unit IV	
0	www.youtube.com/watch?v=WWjldCmRteg
-	www.youtube.com/watch?v=syRQTHF88eQ
1	nptel.ac.in/courses/113/104/113104012/
-	www.youtube.com/watch?v=vS3S1KfNLhE
Unit V	•
-	nptel.ac.in/courses/117/106/117106033/
-	www.digimat.in/nptel/courses/video/108107129/L04.html
1	www.digimat.in/nptel/courses/video/117105147/L01.html
	www.coursera.org/lecture/averagedswitchmodelingandsimulation/spice-simulation- e-pJ99m

NPTEL course video link: https://nptel.ac.in/courses/117/106/117106033/

	M. TECH FIRST YEAR			
Course Code	AMTVL0113	Ľ	ΓР	Credit
Course Title	Analog IC Design	3	00	03
Course Object		-		
	To develop the ability to design and analyze MOS based			
	Analog VLSI circuits.			
2	To analyze the performance of single stage amplifier			
3 '	To develop the skills to design Differential Amplifier			
	circuits for a given specification.			
	Analyze the frequency response of the different			
	configurations of an amplifier			
	To provide the knowledge of operational amplifier & feedback topologies.			
Pre-requisites	Basic electronics devices, Semiconductor & Amplifiers			
	Course Contents / Syllabus			
01111-1	BASIC MOS DEVICE PHYSICS			hours
	tions, MOSFET as a Switch, MOS I/V Characteristics, Sec			
	els, MOS Device Capacitances, NMOS versus PMOS Dev	vices	s, Lon	g-Channel
versus Short-Chanr				0.1
UTIT II	SINGLE-STAGE AMPLIFIERS			8 hours
1	ommon-Source Stage, Common-Source Stage with Resistive I			•
	Load, CS Stage with Current-Source Load, Source Follower, C	Com	mon-(ate Stage,
Cascode Stage, Fol	DIFFERENTIAL AMPLIFIERS			0 1
			<u>(</u> . 1.	8 hours
	Differential Operation, Basic Differential Pair, Commo ith MOS Loads, Gilbert Cell, Passive and Active Current Mi			· ·
	Current Mirrors, Active Current Mirrors, Common-Mode Prope			
	FREQUENCY RESPONSE OF AMPLIFIERS		5	8 hours
0111111	tions, Miller Effect, Association of Poles with Nodes, Com	nmo	n-Sou	
	Common-Gate Stage, Cascode Stage, Differential Pair, Noise			
	es, Effect of Loading, Effect of Feedback on Noise			
	OPERATIONAL AMPLIFIERS			8 hours
	tions, Performance Parameters, One-Stage Op Amps, Two-Sta	age	Op Ai	
	rison, Common-Mode Feedback. Input Range Limitations			
Supply Rejection.				
Course Outco	me: After successful completion of this course studen	nts v	vill b	e able to
	Draw the equivalent circuits of MOS based Analog VLSI an	nd		
	analyse their performance.			
CO 2	Design analog VLSI circuits for a given specification.			
	Analyse the frequency response of the different configuration of an amplifier.	ns		
CO 4 .	Analyse the feedback topologies involved in the amplifier design.			
	Appreciate the design features of the differential amplifiers.			

Text books
1. Razavi, "Design of Analog CMOS Integrated Circuits", 2nd Edition, McGraw Hill Edition
2016.
2. Paul. R.Gray&Robert G. Meyer, "Analysis and Design of Analog Integrated Circuits",
Wiley, 5th Edition, 2009.
3. R. Gregorian and Temes, "Analog MOS Intgrated Circuits for Signal Processing", Wiley
Publications
Reference Books
1. Ken Martin, "Analog Integrated Circuit Design", Wiley Publications.
2. Sedra and Smith, "Microelectronic Circuits", Oxford Publications.
3. B.Razavi, "Fundamentals of Microelectronics", Wiley Publications

	M. TECH FIRST YEAR			
Course Code	AMTVL0114 I	T	Р	Credit
Course Title		b 0		03
Course Object	ive:			
1	To analyze the basic stages of manufacturing and cryst	tal g	rowt	h.
2	To evaluate the process of wafer preparation and oxida			
3	To analyze the lithography and etching process			
4	To explain process of diffusion and ion implantation.			
5	To learn the basic process involved in metallization and	d pa	ckag	ging
Pre-requisites:	Basics of semiconductors and their properties.			
	Course Contents / Syllabus			
UNIT-I	OVERVIEW OF SEMICONDUCTOR INDUSTRY	ľ	8	hours
Semiconductor m Semiconductor Sil Quality.	conductor industry, Process and Product Trends, Stages naterial properties, Crystal growth, Basic wafer fabri licon Preparation, Czochralski (CZ) method, Float zone,	icati	on	operations,
UNIT-II	WAFER FABRICATION			8 hours
Layering , Patter	reparation, Wafer Terminology, Basic Wafer-Fabric rning, Doping, Heat treatments, Circuit design, m ss, Oxidation: Dry and wet oxidation, Clean room Constr	asks	s, E	-
UNIT-III	LITHOGRAPHY AND ETCHING			8 hours
Ten step patternin	g process, Lithography: Optical Lithography, Electron	bea	m li	thography,
Photo masks, Wet	Chemical Etching, Dry etching Wet etching.			
UNIT-IV	DOPING AND DEPOSITION			8 hours
Implantation: Ion	Distions: Diffusion process steps, deposition, Drive- Implantation Technique, Implantation Equipment, C w pressure CVD systems, Plasma enhanced CVD systems beam epitaxy.	CVD	ba	sics, CVD
UNIT-V	METALLIZATION AND PACAKAGING			8 hours
Metallization: M Deposition, Vacuu Types, Packaging	Ietallization Application, Metallization Choices, Im Deposition, Sputtering Apparatus. Packaging of VLS Design Consideration, Package Fabrication Technologie ne: After successful completion of this course stude	SI de es.	vice	l Vapour s: Package
CO 1	Analyze the basic stages of manufacturing and crystal	grov	vth.	
CO 2	Evaluate the process of wafer preparation and oxidation	n.		
CO 3	Analyze the lithography and etching process.			
CO 4	Explain the process of diffusion and ion implantation.			
CO 5	Learn the basic process involved in metallization and p	back	agin	g
Text books				
	, Microchip fabrication, McGraw Hill, 1997.			

2. S.M. Sze, VLSI technology, McGraw-Hill Book company, NY, 1988

Reference Books

1. Wani-Kai Chen (editor), The VLSI Hand book, CRI/IEEE press, 2000

2. C.Y. Chang and S.M. Sze, ULSI technology, McGraw Hill, 2000

3. S.K. Ghandhi, "VLSI Fabrication Principles", Willy-India Pvt. Ltd, 2008.

4. J. D. Plummer, M. D. Deal and Peter B. Griffin, "Silicon VLSI Technology: Fundamentals, Practice and Modeling", Pearson Education Publication, 2009

	M. TECH FIRST YEAR		
Course Code	AMTVL0115	LT P	Credit
Course Title	Clean Room Technology And Maintenance	300	03
Course Object	ve:		I
<u>1</u>		ancillary	
	cleanrooms.	-	
2	Knowledge about clean room fabrication environment.		
3	Identify the various filtration mechanisms.		
4 5	Categorize cleanroom testing and monitoring system.		
5	Analyze air quantities, pressure differences and clean red disciplines.	oom	
Pre-requisites:	Basics of IC Technology		1
	Course Contents / Syllabus		
UNIT-I	INTRODUCTION TO CLEAN ROOM TECHNOL	OGY	8 hours
Clean room star	nroom Classification Standards, Unidirectional air flow ndards, Federal Standards 209 ,ISO standard 146 maceutical, cleanrooms)		
UNIT-II	CLEAN ROOM ENVIRONMENT		8 hours
Design of Turbule	ently Ventilated and Ancillary Cleanrooms, Mini enviro	nments, is	olators and
RABS, Containme	nt zone, Construction and clean build, Design of Unidired FILTRATION MECHANISM	ctional Cle	eanrooms. 8 hours
	ir filtration, Particle removal mechanisms, testing of high	efficiency	
UNIT-IV	TESTING & MONITORING SYSTEM		8 hours
	g and Monitoring, Principles of cleanroom testing, Testin on state, Monitoring of cleanroom.	ng in relat	ion to room
	CLEAN ROOM STANDARD PARAMETERS		8 hours
UNIT-V Measurement of A	CLEAN ROOM STANDARD PARAMETERS air Quantities and Pressure Differences, Air movement of m containment leak testing.	control, Re	8 hours
UNIT-V Measurement of A methods, Cleanroo	ir Quantities and Pressure Differences, Air movement of	,	ecovery test
UNIT-V Measurement of A methods, Cleanroo	ir Quantities and Pressure Differences, Air movement om containment leak testing.	ts will be a	ecovery test
UNIT-V Measurement of A methods, Cleanroo Course Outcor	ir Quantities and Pressure Differences, Air movement of m containment leak testing. ne: After successful completion of this course student	ts will be a	ecovery test
UNIT-V Measurement of A methods, Cleanroo Course Outcon CO 1	Air Quantities and Pressure Differences, Air movement of m containment leak testing. ne: After successful completion of this course student Specify cleanroom standards and ancillary cleanrooms.	ts will be a	ecovery test
UNIT-V Measurement of A methods, Cleanroo Course Outcor CO 1 CO 2	Air Quantities and Pressure Differences, Air movement of m containment leak testing. ne: After successful completion of this course student Specify cleanroom standards and ancillary cleanrooms. Explain about clean room fabrication environment.	ts will be a	ecovery test
UNIT-V Measurement of A methods, Cleanroo Course Outcon CO 1 CO 2 CO 3	Air Quantities and Pressure Differences, Air movement of the containment leak testing. ne: After successful completion of this course student Specify cleanroom standards and ancillary cleanrooms. Explain about clean room fabrication environment. Identify the surface finishes and filtration mechanisms.	ts will be a	ecovery test
UNIT-V Measurement of A methods, Cleanroo Course Outcon CO 1 CO 2 CO 3 CO 4	 Air Quantities and Pressure Differences, Air movement of m containment leak testing. After successful completion of this course student Specify cleanroom standards and ancillary cleanrooms. Explain about clean room fabrication environment. Identify the surface finishes and filtration mechanisms. Categorize cleanroom testing and monitoring system. Analyze air quantities, pressure differences and clean room 	ts will be a	ecovery test

2. Matts Ramstorp, Introduction to Contamination Control and Cleanroom Technology, Wiley, 2008.

Reference Books

1. Wani-Kai Chen (editor), The VLSI Hand book, CRI/IEEE press, 2000

Link:	
Unit 1	https://www.youtube.com/watch?v=8uGZMyjFugg
Unit 2	https://www.youtube.com/watch?v=YAouXIS_FSU
Unit 3	https://www.youtube.com/watch?v=wSSfOqEQClc
Unit 4	https://www.youtube.com/watch?v=aBIxPo0p7dc
Unit 5	https://www.youtube.com/watch?v=lHmHYWdH8Ug

	M. TECH FIRST YEAR		
Course Code	AMTVL0116	L T P	Credit
Course Title	ULSI Technology	3 0 0	03
Course Objecti	ve:		
1	To study the basics of chip fabrication and clean room	n.	
2	To learn the ion implantation and variousOxidation te	chnologies.	
3	To study the classification of lithographic techniques.	•	
4	To identify various metallization schemes.		
5	To explain the concept of Memories.		
Pre-requisites:	Microelectronics		
^	Course Contents / Syllabus		
UNIT-I	CLEAN ROOM AND WAFER PREPARATION		8 hours
wet chemical etcl	JLSI technology: clean room and safety requirements, Ming techniques ,Microelectronics and microscopy, M for construction analysis, TEM sample preparation tech	ULSI proces	
	• • • •		
annealing; Charact Oxidation: kinetic	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modelling erization of impurity profiles. es of silicon dioxide growth for thick, thin and u	ultra-thin film	y and damage
Solid-state diffusio annealing; Charact Oxidation: kinetic technologies in UL	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modellinerization of impurity profiles. es of silicon dioxide growth for thick, thin and u SI; Characterization of oxide films; high K and low K di	ultra-thin film	y and damage ns. Oxidation JLSI.
Solid-state diffusio annealing; Charact Oxidation: kinetic technologies in UL	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modellinerization of impurity profiles. ess of silicon dioxide growth for thick, thin and uses. SI; Characterization of oxide films; high K and low K distribution LITHOGRAPHIC TECHNIQUES	ultra-thin film	y and damage ns. Oxidation JLSI.
Solid-state diffusion annealing; Charact Oxidation: kinetic technologies in UL UNIT-III Photolithography to Chemical Vapour dioxide, silicon ni implantation and Metallization and i	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modelling erization of impurity profiles. es of silicon dioxide growth for thick, thin and u SI; Characterization of oxide films; high K and low K di LITHOGRAPHIC TECHNIQUES echniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition tride and metal films; epitaxial growth of silicon; mode substrate defects, Dielectrics and isolation, Silicide nterconnects.	ultra-thin film ielectrics for t ion of polys delling and te	y and damage ns. Oxidation JLSI. 9 hours ilicon, silicon chnology. Ion and salicide,
Solid-state diffusion annealing; Characte Oxidation: kinetice technologies in UL UNIT-III Photolithography te Chemical Vapour dioxide, silicon ni implantation and Metallization and i UNIT-IV	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modelling erization of impurity profiles. es of silicon dioxide growth for thick, thin and uses of silicon dioxide films; high K and low K distribution of oxide films; high K and low K distribution of oxide films; high K and low K distribution for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition techniques: CVD techniques for deposition tride and metal films; epitaxial growth of silicon; mode substrate defects, Dielectrics and isolation, Silicide interconnects. METALLIZATION TECHNIQUES	ultra-thin film ielectrics for t ion of polys delling and te es, polycide	ns. Oxidation JLSI. 9 hours ilicon, silicon chnology. Ion and salicide, 8 hours
Solid-state diffusion annealing; Characte Oxidation: kinetic technologies in UL UNIT-III Photolithography te Chemical Vapour dioxide, silicon nir implantation and Metallization and Metallization and Metallization schemer Metallization schemer	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modelling erization of impurity profiles. es of silicon dioxide growth for thick, thin and u SI; Characterization of oxide films; high K and low K di LITHOGRAPHIC TECHNIQUES echniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition tride and metal films; epitaxial growth of silicon; mode substrate defects, Dielectrics and isolation, Silicide nterconnects.	ultra-thin film ielectrics for t ion of polys delling and te es, polycide l interconnect erials, TEM i	y and damage ns. Oxidation JLSI. 9 hours ilicon, silicon and salicide, 8 hours ts; multilevel n under bump
Solid-state diffusion annealing; Characte Oxidation: kinetice technologies in UL UNIT-III Photolithography te Chemical Vapour dioxide, silicon ni implantation and Metallization and Metallization and Metallization schemetallization and	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modelling erization of impurity profiles. es of silicon dioxide growth for thick, thin and u.SI; Characterization of oxide films; high K and low K di LITHOGRAPHIC TECHNIQUES echniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition tride and metal films; epitaxial growth of silicon; modeling substrate defects, Dielectrics and isolation, Silicided nterconnects. METALLIZATION TECHNIQUES sputtering techniques. Failure mechanisms in metal mes. TEM in failure analysis, Novel devices and mate	ultra-thin film ielectrics for t ion of polys delling and te es, polycide l interconnect erials, TEM i	y and damage ns. Oxidation JLSI. 9 hours ilicon, silicon and salicide, 8 hours ts; multilevel n under bump tion TEM in
Solid-state diffusion annealing; Characte Oxidation: kinetic technologies in UL UNIT-III Photolithography te Chemical Vapour dioxide, silicon nir implantation and Metallization and Metallization and Metallization and Metallization and microelectronics. UNIT-V DRAM cell with p	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modelling erization of impurity profiles. es of silicon dioxide growth for thick, thin and uteration of silicon dioxide films; high K and low K distribution of oxide films; high K and low K distribution of oxide films; high K and low K distribution for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition techniques: CVD techniques for deposition substrate defects, Dielectrics and isolation, Silicide interconnects. METALLIZATION TECHNIQUES sputtering techniques. Failure mechanisms in metal mes. TEM in failure analysis, Novel devices and mate advanced electronics packaging technologies, High	ultra-thin film ielectrics for t ion of polys delling and te es, polycide l interconnec erials, TEM i gh – resolut	y and damage ns. Oxidation JLSI. 9 hours ilicon, silicon echnology. Ion and salicide, 8 hours ts; multilevel n under bump ion TEM in 6 hours
Solid-state diffusion annealing; Characte Oxidation: kinetice technologies in UL UNIT-III Photolithography te Chemical Vapour dioxide, silicon ni implantation and Metallization and Metallization and Metallization schere metallization and microelectronics. UNIT-V DRAM cell with p III: DRAM cell with	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modelling erization of impurity profiles. ess of silicon dioxide growth for thick, thin and utorest solution of oxide films; high K and low K distribution of oxide films; high K and low K distribution of the silicon of oxide films; high K and low K distribution techniques: CVD techniques for deposition techniques: Dielectrics and isolation, Silicide nterconnects. METALLIZATION TECHNIQUES sputtering techniques. Failure mechanisms in metal mes. TEM in failure analysis, Novel devices and mate advanced electronics packaging technologies, Hig ULSI DEVICES data capacitor, ULSI devices II: DRAM cell with stack	ultra-thin film ielectrics for to ion of polys delling and te es, polycide l interconnect erials, TEM i gh – resolut ced capacitor,	y and damage ns. Oxidation JLSI. 9 hours ilicon, silicon echnology. Ion and salicide, 8 hours ts; multilevel n under bump ion TEM in 6 hours ULSI devices
Solid-state diffusion annealing; Characte Oxidation: kinetice technologies in UL UNIT-III Photolithography te Chemical Vapour dioxide, silicon ni implantation and Metallization and Metallization and Metallization schere metallization and microelectronics. UNIT-V DRAM cell with p III: DRAM cell with	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modelline erization of impurity profiles. ess of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide films; high K and low K distributed in the construction of oxide films; high K and low K distributed in the construction of oxide films; high K and low K distributed in techniques for VLSI/ULSI; Mask generation. deposition techniques: CVD techniques for deposition techniques: CVD techniques for deposition techniques: CVD techniques for deposition techniques. The provided the provided of the provided interconnects. METALLIZATION TECHNIQUES sputtering techniques. Failure mechanisms in metal mes. TEM in failure analysis, Novel devices and mate advanced electronics packaging technologies, High duration of the provided of the p	ultra-thin film ielectrics for to ion of polys delling and te es, polycide l interconnect erials, TEM i gh – resolut ced capacitor,	y and damage ns. Oxidation JLSI. 9 hours ilicon, silicon echnology. Ion and salicide, 8 hours ts; multilevel n under bump ion TEM in 6 hours ULSI devices
Solid-state diffusion annealing; Characte Oxidation: kinetice technologies in UL UNIT-III Photolithography te Chemical Vapour dioxide, silicon ni implantation and Metallization and Metallization and Metallization scher metallization and microelectronics. UNIT-V DRAM cell with p III: DRAM cell with	IMPURITY INCORPORATION on modelling and technology, Ion implantation: modelline erization of impurity profiles. es of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for thick, thin and uses of silicon dioxide growth for this course student dioxide growth for the stack diverse of this course student dioxide growth for the stack diverse of the stack diverse for the	ultra-thin film ielectrics for U ion of polys delling and te es, polycide l interconnect erials, TEM i gh – resolut ced capacitor, ts will be abl	y and damage ns. Oxidation JLSI. 9 hours ilicon, silicon echnology. Ion and salicide, 8 hours ts; multilevel n under bump ion TEM in 6 hours ULSI devices

CO 4	Explain and analyze metallization schemes.	
CO 5	Design semiconductor memories.	

Text books

1. S.M. Sze(2nd Edition)"VLSI Technology", McGraw Hill Companies Inc.

2. Chih-Hang Tung, George T.T. Sheng, Chih-Yuan Lu, ULSI Semiconductor Process Technology Atlas, John Wiley & Sons, 2003.

3. C.Y. Chang and S.M. Sze (Ed), "ULSI Technology", 2000, McGraw Hill Companies Inc.

Reference Books

1. Stephena, Campbell, "The Science and Engineering of Microelectronic Fabrication", Second Edition, Oxford University Press.

2. James D. Plummer, Michael D. Deal, "Silicon VLSI Technology" Pearson Education Reading.

Course CodeAMTVL0201LT PCreeCourse TitleDigital Design using FPGA and CPLD3 0 00.Course Objective:	3 table
Course TitleDigital Design using FPGA and CPLD3 0 0Course Objective:1To study finite state machines and its realization.1To study finite state machines and its realization.2To study asynchronous Sequentialmachine.3To learn Designing of Digital logic using PLD.4To get knowledge of different FPGA series.5To study different CPLD series.Pre-requisites:Basics of CMOS and Fabrication.UNIT-IFINITE STATE MACHINE (FSM)8 hoursIntroduction, Design Strategies, Mealy & Moore model, Realization of State Diagram & state from verbal description, Minimization of State Table from completely & Incompletely specState Machine, Introduction to Algorithmic State Machine.UNIT-IIASYNCHRONOUS SEQUENTIAL CIRCUIT8 hoursIntroduction to Asynchronous Sequential Machine (ASM), fundamental & pulse modeAsynchronous Sequential machine, Secondary State Assignments in Asynchronous Sequential	table
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Asynchronous Sequential machine, Secondary State Assignments in Asynchronous Sequential	<i>i</i> ul S
UNIT-IIIPROGRAMMABLE LOGIC DEVICES (PLD)8 ho	ours
Introduction, Architecture, Features & Digital Design of ROM, EPROM, EEPROM, Flash Memory, PLA, PAL & PGA, Design of a keypad scanner using PLD.	2
UNIT-IV FIELD PROGRAMMABLE GATE ARRAY (FPGA) 8 ho	ours
Logic blocks, Routing architecture, Design flow, Technology Mapping for FPGA. Xilinx FPGA XC4000, Comparative Study of Xilinx (ZU11EG) & Intel (Stratix 10 SX650 s from Altera) with reference to cortex A53.	eries
UNIT-V COMPLEX PROGRAMMABLE LOGIC DEVICES 8 hc (CPLD)	ours
Altera series – Max 5000/7000 series and Altera FLEX logic- 10000 series CPLD, AMD's- C. (Mach 1 to 5), Cypress FLASH 370 Device technology, Lattice plsi architectures – 3000 series Speed performance and system programmability. Course Outcome: After completion of this course students will be able to	
CO 1 Realize finite state machines.	
CO 2 Formulate asynchronous Sequentialmachine.	
CO 3 Design Digital logic using PLD.	
CO 4 Explain different FPGA series.	
CO 5 Explain different CPLD series.	
Text books	

- 1. P. K. Chan& S. Mourad, Digital Design using Field Programmable Gate Array, Prentice Hall.
- 2. Charles H Roth, Jr., "Digital Systems Design Using VHDL", PWS, 1998.
- 3. S. Trimberger, Edr., Field Programmable Gate Array Technology, Kluwer Academic Pub.

Reference Books

- 1. J. Old Field, R. Dorf, Field Programmable Gate Arrays, John Wiley& Sons, Newyork.
- 2. S.Brown, R.Francis, J.Rose, Z.Vransic, Field Programmable GateArray, Kluwer Pub.
- 3. Richard FJinder, "Engineering Digital Design," Academic press

	M. TECH FIRST YEAR					
Course Code	AMTVL0202	LT P	Credit			
Course Title	Low Power VLSI Design	300	03			
Course Objectiv	/e:					
1	To provide the knowledge of Low Power VLSI C	hips and				
	different losses associated with the CMOS Devices					
2	To provide the knowledge of Power estimation Simulation	n Power				
	analysis and Probabilistic power analysis of Design					
3	To provide the knowledge of circuit level and Logic level	-				
4	To provide the knowledge of Low Power Architecture and					
5	To provide the basic knowledge of Low Power Clock Dis	tribution				
	Algorithm & Architectural Level Methodologies					
Pre-requisites:	CMOS VLSI Design, Digital logic Design.					
	Course Contents / Syllabus					
UNIT-I	INTRODUCTION & DEVICE AND TECHNOLOGY	7	8 hours			
	IMPACT ON LOW POWER					
	ls for Low Power VLSI Chips, Sources of power dissipation					
	w power approaches, Physics of power dissipation in CMC					
	logy impact on low power: Dynamic dissipation on low po		sistor sizing			
	ness, Impact of technology Scaling, Technology & Device i					
UNIT-II	POWER ESTIMATION SIMULATION POWER AN	ALYSIS	8 hours			
	& PROBABILISTIC POWER ANALYSIS					
	Simulation Power analysis: - SPICE circuit simulators, G					
· •	ive Power Estimation, Static State Power, Gate level Capac					
	analysis, Data Correlation Analysis in DSP systems. Monte					
	r analysis:- Random Logic Signals. Probability & frequence chniques, Signal Entropy.	ey, Probabi	lisuc			
	LOW POWER DESIGN		0 h a			
UNIT-III		· TT' 1	8 hours			
	er Consumption in circuit level, Flip Flop & Latches des	ign, High	Capacitance			
node, Low power d	•	a a hima a m	anding Dra			
U	Reorganisation, Signal gating, Logic encoding, state m	lachine en	coding, Pre			
computation logic	LOW POWER ARCHITECTURE AND SYSTEM		Q h a u u a			
	UNIT-IVLOW POWER ARCHITECTURE AND SYSTEM8 hoursPower & Performance Management, Switching Activity Reduction, Parallel Architecture with					
	Flow graph Transformation, Low Power Arithmetic Co					
	riow graph Transformation, Low Power Anumetic Co	mponent,	Low Fower			
Memory Design	LOW POWER CLOCK DISTRIBUTION & ALGOR	ІТНМ	Q harris			
UNIT-V	& ARCHITECTURAL LEVEL METHODOLOGIES		8 hours			
Low Power Clas	k Distribution: -Power dissipation in clock distributi		driver Ve			
	zero skew Vs tolerable skew chip and package co-design of					
	itectural Level Methodologies: -Introduction, Design flo					
0	zation, Architectural level estimation and synthesis	,				
and optimit						

Course Outco	Ome: After successful completion of this course students will be able to
CO 1	Identify different losses associated with the CMOS Devices.
CO 2	Explain the concept of Power estimation Simulation Power analysis and Probabilistic Power analysis of Design.
CO 3	Identify circuit and logic level low power design.
CO 4	Analyze the Low Power Architecture and system.
CO 5	Explain Low Power Clock Distribution Algorithm.
Text books	
1. Gary K.	Yeap, Practical Low Power Digital VLSI Design, KAP 2007
2. Rabaey,	Pedram, "Low power design methodologies" Kluwer Academic, 1997
Reference Bo	oks
1. Kaushik	Roy, Sharat Prasad, "Low-Power CMOS VLSI Circuit" Wiley 2000

		M. TECH FIRST YEAR		
Course C	Code	AMTVL0251	LTP	Credit
Course Title		Digital Design using FPGA and CPLD Lab	0 0 4	02
Pre-requ	isites: Ba	sics Knowledge of Digital Electronics & Digital System Design		
Sr. No.	List of	f Experiment		
1	Demon	stration of FPGA and CPLD Boards.		
2	Design	& Implement the Boolean Expression Y=AB+BC+CA on CPLD.		
3	Design	& Implement Full adder and Full Subtractor on CPLD.		
4.	Design	& Implement (i) 2-bit comparator and (ii) 2-bit multiplier (iii) 8x1 M	fultiplexer	on CPLD.
5	Design	& Implement S-R, J-K, D and T Flip Flops on FPGA.		
6	Design FPGA.	& Implement (i) Universal shift register (ii) 4- bit UP-DOWN S	ynchronous	Counter on
7	Design	& Implement the (i) 4-bit ALU (ii) 8- bit SRAM on FPGA.		
8	Design	& Implement 7- Segment Display Driver circuit using CPLD.		
9	Design	& Implement Sequence Detector Circuit to detect given sequence 10	101010 on	FPGA.
10	Modell	ing and Implementation of UART on FPGA.		
Lab Cou	rse Outo	come: After completion of this course students will be able to		
CO 1	Design	& Implement the Combinational Logic Circuits on CPLD.		
CO 2		& Implement the Sequential Logic Circuits on CPLD.		
CO 3	Design	& Implement the Memories on FPGA.		
CO 4	Design	& Implement UART on FPGA.		
Link:				
1	https://	www.youtube.com/watch?v=9mpRF6bAY1g		
2	https://	www.youtube.com/watch?v=EGDHXynlXMk		
3	https://	www.youtube.com/watch?v=H2GyAIYwZbw		
4	https://	www.youtube.com/watch?v=WKZgK3BKDIo		
5		www.youtube.com/watch?v=s3Dk4CEfNg4&list=PLJ5C_6qdAvBE index=6	LELTSPgz	YkQg3Hgcl

	M. TECH FIRST YEAR				
Course Code	AMTVL0252	LT P	Credit		
Course Title	Low Power VLSI Design Lab	004	02		
Software Tool: SO 1. ANA 2. ANA	 PFTWARE TOOL: CADENCE – Tool Bundle Consisti ALOG & MIXED SIGNAL DESIGN FRONT END TO Virtuoso(R) Spectre(R) Simulator REL MMSIM 7.1 Virtuoso(R) Schematic Editor XL REL IC 6.1.0 ALOG BACK END TOOL Virtuoso(R) Layout Suite XL REL IC 6.1.0 VITUOSO(R) Layout Suite XL REL IC 6.1.0 VITUOSO(R) Layout Suite XL REL IC 6.1.0 VITUOSO(R) SCO Encounter - XL (aka Cadence (R) SOC Encounter Name of Experiment 	ng of: OLS			
1	I-V characteristics of long and short-channel MOSFI	ET transisto	ors in CMOS		
	technology.				
2	The gate capacitance of an MOS transistor. (Gate Capac	itance v/s V	/GS).		
3	The impact of device variations on static CMOS inverte				
4	The VTC of CMOS inverter as a function of supply vol	tage and sub			
5	Dynamic power dissipation due to charging and dischar	ging capaci	tances.		
6	Short-circuit currents during transients and impact of loc circuit current in a CMOS inverter.	ad capacitar	nce on short-		
7	The VTC of a two-input NAND & NOR data dependent	cy.			
8	The variable-threshold CMOS inverter and Combination	-			
9	The low-power / low voltage D-Latch circuit.				
10	Low-power circuits a. The Full Adder b. The Binary Adder c. The Multiplier d. The Shifter. e. The SRAM Cell f. The DRAM Cell				
Lab Course Ou	itcome: After completion of this course students are a	ble to			
CO 1	Study and analyze the various parameters of MOS Tran				
CO 2	Study and analyze the different parameters of CMOS design.	inverter fo	or low power		
CO 3	Design and implement the combinational digital circuits	s for low po	wer circuits.		
CO 4	Design and implement the sequential digital circuits for	low power	circuits.		
Link:					
Unit 1	https://www.youtube.com/watch?v=TFOO1JA112Y https://youtu.be/ruClwamT-R0				
Unit 2	Jnit 2 https://www.analog.com/en/design-center/design-tools-and-calculators/ltspice simulator.html https://www.youtube.com/watch?v=OgO1gpXSUzU				

	https://nptel.ac.in/courses/111/106/111106134/	
Unit 3	https://nptel.ac.in/courses/106/105/106105034/ https://www.youtube.com/watch?v=dqcfYTePRxQ https://www.youtube.com/watch?v=rEeqxozkdZ0	
Unit 4	https://www.digimat.in/nptel/courses/video/106105034/L37.html	
Unit 5	https://nptel.ac.in/courses/106/105/106105161/	

	M. TECH FIRST YEAR		
Course Code	AMTVL0211	LTP	Credit
Course Title	VLSI Testing and Testability	300	03
Course Objectiv	/e:		
1	To provide an in-depth understanding of the importance	e and	
	principle of testing and verification of faults affecting V circuits.		
2	To provide the knowledge of the testing and testability combinational circuits.	of	
3	To provide the knowledge of the testing and testability sequential circuits.	of	
4	To provide an in-depth understanding of the memory de testing methods.	esign and	
5	To provide the basic knowledge of Built in self-test (BI Techniques.	(ST)	
Pre-requisites:D	igital and analog IC fabrication.		
	Course Contents / Syllabus		
UNIT-I	INTRODUCTION TO VLSI TESTING AND FAUL MODELING	T	10 hours
Importance and Prir	ciple of testing, Challenges in VLSI testing, Levels of ab	ostractions	in VLSI
-	vs. Structural approach to testing, Complexity of the testing		
Testing, DC and AC	C parametric tests		
Fault Modeling: Stu	ick at fault, fault equivalence, fault collapsing, fault domi		t simulation
UNIT-II	TESTING AND TESTABILITY OF COMBINATION CIRCUITS	ONAL	8 hours
	sics: Test generation algorithms, Random test generation, its, Boolean difference, Path sensitization, D – algorithm circuit design		
UNIT-III	TESTING AND TESTABILITY OF SEQUENTIAL CIRCUITS		8 hours
generation based on	I circuits as iterative combinational circuits, state table ve circuit structure, Sequential ATPG, s, scan path technique (scan design), partial scan, Bounda		test
UNIT-IV	MEMORY, DELAY, FAULT AND IDDQ TESTING	-	6 hours
Testable memory de	esign, RAM fault models, Test algorithms for RAM, Dela ng methods, Limitations of IDDQ testing	ay faults, D	
UNIT-V	BUILT IN SELF-TEST (BIST) TECHNIQUES		8 hours
	IST): Design rules, Exhaustive testing, Pseudo-random to onse analysis, Logic BIST architectures, Introduction to T	•	udo-exhaustive
Course Outcom	e: After successful completion of this course students	s will be ab	ole to
CO 1	Apply the concepts in testing which can help them better yield in IC design	n design a	

CO 2	Analyse the various test generation methods for combinational circuits.	
CO 3	Analyse the various test generation methods for sequential circuits.	
CO 4	Identify the design for testability methods for different memory circuits.	
CO 5	Recognize the BIST techniques for improving testability.	

Text books

- 1. An Introduction to Logic Circuit Testing Parag K. Lala, (Morgan & Claypool Publishers)
- 2. Essentials of Electronic Testing for Digital, Memory & Mixed Signal VLSI Circuits Michael L. Bushnell and Vishwani D. Agrawal, (Kluwar Academic Publishers 2000)
- 3. Digital System Testing and Testable Design M. Abramovici, M.Breuer, and A. Friedman (Jaico Publishing House)

Reference Books

- 1. Introduction to Formal Hardware Verification Thomas Kropf (Springer)
- VLSI Test Principles and Architectures Design for Testability W.W. Wen (Morgan Kaufmann Publishers. 2006)
- 3. Digital Systems and Testable Design M.Abramovici, M.A. Breuer and A.D. Friedman (Jaico Publishing House)
- 4. Design Test for Digital IC's and Embedded Core Systems A.L. Crouch (Prentice Hall International)

Link:	
Unit 1	https://youtu.be/u_XLaTTzXaE
Unit 2	https://nptel.ac.in/courses/106/103/106103116/
Unit 3	https://nptel.ac.in/courses/106/103/106103116/
Unit 4	https://nptel.ac.in/courses/106/103/106103116/
Unit 5	https://nptel.ac.in/courses/106/103/106103116/

	M. TECH FIRST YEAR			
Course Code	AMTVL0212	L T P Credi		
Course Title	VLSI DSP Architectures3 0 0			
Course Object	ive:		I	
1	To explain basics of DSP processors and micro	program	nming	
	approaches.		-	
2	To learn building a data path and control path.			
3	To outline pipelining and pipe lined data path.			
4	To analyzeA/D and D /A converters and DSP computa		ors.	
5	To identify thearchitectures for programmable	digital	signal	
	processing devices.			
Pre-requisites	VLSI DSP Architecture			
	Course Contents / Syllabus			
UNIT-I	BASICS OF DSP PROCESSORS		8 h	ours
	s of Instruction set architectures of DSP processo	rs, Micr		
	plementation of control part of the processor, CPU per			
evaluating perform				
UNIT-II	DATA PATH			9 hour
Introduction to lo	gic design conventions, building a data path, a simple in	nplemen	tation s	cheme,
	mentation, simplifying control design.	1		
UNIT-III	PIPELINING			9 hour
An overview of p	ipelining, a pipe lined data path, pipe lined control, data	hazards a	and forv	varding,
data hazards, brar	ch hazards, advanced pipelining: extracting more perfor	mance.		_
UNIT-IV	CONVERSIONS			8 hour
Number formats	for signals and coefficients in DSP systems, dynam	nic range	e and p	recision
sources of errors	in DSP implementations, A/D conversion errors, and D	SP comp	outation	al errors
D/A conversion				
UNIT-V	PROGRAMMABLE PROCESSORS			8 hour
architectural feat	architectures for programmable digital signal pro- ures, DSP computational building blocks, bus architess generation unit, speed issues, features for external int	tecture,	data ad	
Course Outco	me: After successful completion of this course stude	nts will	be able	to
CO 1	Identify basics of DSP processors and micro approaches.	prograr	nming	
CO 2	Learn building a data path and control path.			
CO 3	Analyze pipelining and pipe lined data path.			
CO 4	CalculateA/D and D/A converters and DSP computation	onal erro	rs.	
CO 5	Implement architectures for programmable digital sig devices.	nal proc	essing	
Text books				
	and J.L Hennessy, "Computer Organization and Design	: Hardwa	are/ Sof	tware

2. A. S Tannenbaum, "Structural Computer organization", 4th Ed., Prentice-Hall, 1999. **Reference Books**

 W. Wolf, "Modern VLSI Design: System on Silicon", 2nd Ed., Person Education,1998.
 Keshab Parhi, "VLSI Digital Signal Processing system design and implementations", Wiley1999.

			M. TECH FIRST YI	EAR		
Cour	rse Code		AMTVL0213		LT P	Credit
Cour	rse Title		Full Custom Design		300	03
	rse Obje	ctive				
1			be familiar with the schematic fundamenta	ls and lavout de	esigns fl	ow.
2			come to know about standard library cells			
	basic cel		ý		51	
3	Students	will t	be able to design interconnect layout and k	now special ele	ctrical	
	requirem					
4			be able to incorporate special design rules		ge rules	S
5	Students	will t	be able to learn various kind of CAD tools			
Pre-	requisite	s:Bas	ics of VLSI			
			Course Contents / Syl	llabus		
UNI	T-I		INTRODUCTION			8 hours
Introd	luction: S	chema	tic fundamentals, Layout design, Intro	oduction to Cl	MOS V	/LSI manufacturing
proces	sses, Laye	rs and	d connectivity, Process design rules Sign	nificance of ful	l custor	m IC design, layout
desigr	n flows.					
UNI	T-II		SPECIALIZED BUILDING BLOCKS	5		8 hours
Advar	nced techn	iques	for specialized building blocks Standard	cell libraries, Pa	id cells	and Laser fuse cells,
Power	r grid Cloc	k sigr	als and Interconnect routing.			
UNI			LAYOUT DESIGNS			8 hours
	-	out de	esign, Special electrical requirements, La	yout design tecl	nniques	to address electrical
charac	cteristics.					
UNI			LAYOUT CONSIDERATIONS			8 hours
			s due to process constraints Large metal			
		ules, I	atch-up and Guard rings, Constructing th	e pad ring, Min	imizing	
UNI			LAYOUT CAD TOOLS			8 hours
Prope	r layout C.	AD to	ols for layout, Planning tools, Layout gen	eration tools, Su	apport to	ools.
Cour	rse Outco	ome:	After successful completion of this cou	irse students w	ill be a	ble to
CO	01 I	Design	layout with schematic.			
CO	O 2 I	Differe	ntiate standard cells and other types of cells	lls.		
CO	O 3 I	The Do the	electrical connections and interconnect la	yout designs.		
CO	CO 4 Tackle with the minimization of stress effects.					
CO	05 I)emor	strate the layout tools, generation tools, et	tc.		
Text	books					
1.Dan	Clein, CN	AOS I	C Layout Concepts Methodologies and To	ools, Newnes, 2	000.	
			The Art of Analog Layout, 2nd Edition, P			
<u>2.1(</u> uy						
	rence Bo	oks				
M. TECH FIRST YEAR						
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Course Code	AMTVL0214	LT P	Credit			
Course Title	MEMS Sensor Design	300	03			
Course Object	0	000				
1		brication				
2	To provide the knowledge about Mechanics of Bean Diaphragm Structures.	n and				
3	To provide the knowledge about drag effect of a flui damping and its models.	d, Air				
4	To provide the knowledge of Electrostatic Actuation	1.				
5	To provide the basic knowledge of MEMS Structure	es and				
	Systems in RF applications.					
Pre-requisites:	Basics of sensors.					
	Course Contents / Syllabus					
UNIT-I	INTRODUCTION TO MEMS		8 hours			
MEMS Fabricatio	on Technologies, Materials and Substrates for M	EMS, Pro	cesses for			
Micromachining,	Sensors/Transducers, Piezoresistive Effect, Piezoelec	tricity, Pie	zoresistive			
Sensor.						
UNIT-II	MECHANICS OF BEAM AND DIAPI STRUCTURES	HRAGM	8 hours			
Stress and Strain,	Hooke's Law. Stress and Strain of Beam Structure	s: Stress,	Strain in a			
Bent Beam, Bendi	ing Moment and the Moment of Inertia, Displacemen	t of Beam	Structures			
Under Weight, Be	nding of Cantilever Beam Under Weight.					
UNIT-III	AIR DAMPING		8 hours			
Drag Effect of a F	luid: Viscosity of a Fluid, Viscous Flow of a Fluid, I	Drag Force	Damping,			
The Effects of A	ir Damping on Micro-Dynamics. Squeeze-film Air	Damping:	Reynolds'			
Equations for Squ	eeze-film Air Damping, Damping of Perforated Th	ick Plates.	Slide-film			
Air Damping: Ba	sic Equations for Slide-film Air Damping, Couette-	flow Mod	el, Stokes-			
flow Model.						
UNIT-IV	ELECTROSTATIC ACTUATION		8 hours			
of Mechanical Ac	es, Normal Force, Tangential Force, Fringe Effects, etuators: Parallel-plate Actuator, Capacitive sensors. Step Voltage Driving, Negative Spring Effect and Vib	Step and	Alternative			
UNIT-V	MEMS STRUCTURES AND SYSTEMS	IN RF	8 hours			
U111-V	APPLICATIONS		o nours			
Signal Integrity	in RF MEMS, Microelectromechanical Reson	nators: C	omb-Drive			
	Resonators, Coupled-Resonator Bandpass Filters,		k Acoustic			
Resonators, Microelectromechanical Switches: Membrane Shunt Switch, Cantilever Series Switch.						
Course Outcome: After successful completion of this course students will be able to						
CO 1	Identify MEMs fabrication Technologies.					

CO 2	Analyse Mechanics of Beam and Diaphragm Structures.
CO 3	Explain drag effect of a fluid, Air damping and its models.
CO 4	Design different Electrostatic Actuators.
CO 5	Explain MEMS Structures and Systems in RF applications.
Text books	
1. Minhang I	Bao, 'Analysis and Design Principles of MEMS Devices', First edition
2005, Else	evier.
2. Nadim Ma	aluf, KirtWilliums, 'An Introduction to Microelectromechanical Systems
Engineerin	ng',2nd ed., Artech House microelectromechanical library.
Reference Boo	ks
1. RS Muller	, Howe, Senturia and Smith, "Micro-sensors", IEEE Press.

M. TECH FIRST YEAR					
Course Code	AMTVL0215	LT P	Credit		
Course Title	Nanoscale Devices: Modeling & Simulation	300	03		
Course Objec	tive:				
1	To introduce novel MOSFET devices and understan	nd the			
	advantages of multi-gate devices				
2	To introduce the concepts of nanoscale MOS transister	or and			
	their performance characteristics				
	To study the various Nano-scaled MOS transistor circuits	s			
4	To study radiation effects in SOI MOSFETs				
5	To study digital circuits and impact of device performan	nce on			
	digital circuits Course Contents / Syllabus				
UNIT-I	MOSFET SCALING		8 hours		
transistors – singl inversion – mo mobility–gatestac		effects -	- volume		
UNIT-II	MOS ELECTROSTATICS		8 hours		
voltage effect - se	CMOSTechnology – Ultimate limits, double gate MO emiconductor thickness effect – asymmetry effect – oxide t urrent – two dimensional confinements, scattering –mobil	hickness			
UNIT-III	SILICON NANOWIRE MOSFETS		10 hours		
Silicon nanowire MOSFETs – Evaluation of I-V characteristics – The I-V characteristics for non- degenerate carrier statistics – The I-V characteristics for degenerate carrier statistics – Carbon nanotube – Band structure of carbon nanotube – Band structure of graphene – Physical structure of nanotube – Band structure of nanotube – Carbon nanotube FETs – Carbon nanotube MOSFETs – Schottky barrier carbon nanotube FETs – Electronic conduction in molecules – General model for ballistic nano transistors – MOSFETs with 0D, 1D, and 2D channels – Molecular transistors – Single electron charging – Single electron transistors					
	in SOI MOSFETs, total ionizing dose effects – single-g		<u>6 hours</u> – multi-		
	le event effect, scaling effects.	Juie 501	1110111		
	DIGITAL CIRCUITS		8 hours		
trade off – mu transconductance	impact of device performance on digital circuits – leak lti VT devices and circuits – SRAM design, analog - intrinsic gain – flicker noise – self heating –band gap vo lifier – comparator designs, mixed signal – successive s.	gcircuit of oltage ref	design – Terence –		

Course Outcome: After successful completion of this course students will be able to			
CO 1	Explain the MOS devices used below 10nm and beyond with		
	an eye on the future		
CO 2	Explain the physics behind the operation of multi-gate		
	systems.		
CO 3	To design circuits using nano-scaled MOS transistors with the		
	physical insight of their functional characteristics		
CO 4	Explain radiation effects in SOI MOSFETs		
CO 5	Explain and designdigital circuits and impact of device		
	performance on digital circuits		
Text books			
1. J P Coli	nge, "FINFETs and other multi-gate transistors", Springer – Series on		
integrate	ed circuits and systems,2008		
2. Mark I	undstrom, Jing Guo, "Nanoscale Transistors: Device Physics,		
Modelin	gand Simulation", Springer,2006		
Reference bo	ooks		
1. M S Lui	ndstorm, "Fundamentals of Carrier Transport", 2nd Ed., Cambridge University		
Press, C	Cambridge UK, 2000		

	M. TECH FIRST YEAR		
Course Code	AMTVL0216	LT P	Credit
Course Title	Physical Design & Automation	300	03
Course Object	ive:		1
1	Students will know how to place the blocks and how to p	artition	
	the blocks while for designing the layout for IC.		
2	Students will be familiar to various kind of VLSI Automa	tion	
	Algorithms.		
3	Students will know the concepts of Physical Design Proce	ss	
	such as Floor planning, Placement algorithms.		
4	Students will learn Global Routing and Detailed Routing		
5	algorithms.		
5 Dra ragnisitasi	Students will learn over the Cell Routing in detail.		
rre-requisites:	Basics of digital IC and data structures. Course Contents / Syllabus		
UNIT-I	LOGIC SYNTHESIS & VERIFICATION		8 hours
	& Verification: Introduction combinational logic synthes	sis Bina	
	re models for High- level synthesis.	515, Dina	
UNIT-II	VLSI AUTOMATION ALGORITHMS		8 hours
	n Algorithms: Partition: problem formulation, classifica	tion of	
	p migration algorithms, simulated annealing & evolutio		
algorithms.			г с
UNIT-III	PLACEMENT, FLOOR PLANNING & PIN ASSIGN	MENT	8 hours
Placement, Floor	Planning & Pin assignment: problem-formulation, simulat	ion-based	l placement
algorithms, other	r placement algorithms, constraint-based floor planni	ng, floo	r planning
algorithms for mix	xed block & cell design. General & channel pin assignment.		
UNIT-IV	GLOBAL ROUTING & DETAILED ROUTING		8 hours
algorithm, line pro Detailed Routing:	Problem formulation, classification of global routing algor obe algorithm, Steiner Tree based algorithm, ILP based appropriate problem formulation, classification of routing algorithms, ayer channel routing algorithms, three-layer channel rout galgorithms.	roaches. single la ting algo	yer routing
	outing & via Minimization: two layers over the cell rou		
	minimization Compaction: problem formulation, one-dime		
	sed Compaction, hierarchical compaction.		compaction,
	me: After successful completion of this course students	will be a	ble to
CO 1	Know how to place the blocks and how to partition the		
	while for designing the layout for IC.		
CO 2	Explain VLSI Design Automation.		
		a Flace	
CO 3	Explain the concepts of Physical Design Process such a planning, Placement and Routing.	s fioor	
	pranning, i racement and Kouting.		

(CO 4	AnalyzeGlobal Routing and Detailed Routing algorithms.	
(CO 5	Decompose large problem into pieces via minimization.	
Text	books		
1.	Naveed	Sherwani, "Algorithms for VLSI Physical Design Automation	n", Kluwer
	Academ	ic Publisher, Second edition.	
Refer	ence Bo	ooks	
1.	Christop	hnMeinel&ThorstemTheobold, "Algorithm and Data Structures	for VLSI
	Design"	, KAP 2002.	
2.	Rolf Dre	chsheler : "Evolutionary Algorithm for VLSI", second edition	
3.	Trimbur	ger," Introduction to CAD for VLSI", Kluwer Academic publisher, 20	02.

	M. TECH FIRST YEAR			
Course Code	AMTVL0217	L	ТР	Credit
Course Title	Embedded Microcontrollers	3	0 0	03
Course Objec	tive:	_		
1	To provide the Basic knowledge of interfa	acing	with	
	Embedded System.	0		
2	To analyse the process design of embedded sys	stem.		
3	To realize the architecture of PIC 16F Microco Series.			
4	To familiar with the fundamentals of ARM Pro Cortex M3 & M4.	ocess	or	
5	To apply the knowledge of ARM Instruction programming.	on S	et for	
Pre-requisites	Digital System design, 8051 Microcontroller			
•	Course Contents / Syllabus			
UNIT-I	TYPICAL EMBEDDED SYSTEMS			8 hours
PLDs, Commerce according to the	bedded system, General purpose and domain ial off the shelf Components (COTS), Memo type of interface, Memory Shadowing, Mem and actuators, Introduction to Communication	ory: ory s	RAM, selectio	ROM, Memory on for embedded
UNIT-II	EMBEDDED SYSTEMS DESIGN PROCE	SS		8 hours
development pro Decision (Hardy Environment (us	m project development, Design issues and o cess, The Embedded Design Life Cycle, Selecti ware and Software partitioning), The Dev e of target machine or its emulator and In- ques, Introduction to BDM, JTAG, and Nexus.	on Pa velop	rocess, ment	The Partitioning and Debugging
UNIT-III	PIC 16F MICROCONTROLLER SERIES			8 hours
Introduction to overview of PIC16F84/PIC16 addressing, and Special features of Timer (PWRT), SLEEP, Code	PIC Microcontroller families (8/16 and 32 b architecture and peripherals, Pin diagra F84A Microcontroller, Memory organization special function registers, parallel and serial of PIC16F84A (OSC Selection, RESET - Power Oscillator Start-up Timer (OST), Interrupts, Protection, ID Locations, In-Circuit Serial erview of PIC 16F877/PIC 16F887A.	m on, c port r-on Wa	and configu ts, tim Reset tchdog	6F series family Architecture of tration, memory er and counters. (POR), Power-up g Timer (WDT),
UNIT-IV	ARCHITECTURE OF ARM CORTEX M3 PROCESSORS	AN	D M4	8 hours
set, Block diagra Operation mode requirements, en barriers, Low po exceptions and ir	Cortex-M3 and Cortex-M4 processors (Proces m, Memory system, Interrupt and exception su es, Registers, Memory System, features, dianness, bit band operations, access permissi wer design and features, low power application terrupts, exception types and interrupt manager NVIC register, SCB register and other special	pport stac ons a n dev nent,	t).Prog ck me and at velopm , vecto	rammer's model, emory, memory tributes, memory nent, overview of r table, exception

interrupt control, configuration control and auxiliary control registers.					
UNIT-V	INSTRUCTION	SETOF CO	RTEX M3	AND M4	8 hours
	PROCESSORS				
Evolution of AR	M ISA, Comparison	n of the instr	uction set in	ARM Corte	ex-M Processors,
Unified Assemb	ly Language, Addr	essing modes	s, Instruction	n set, Progra	am flow control
(branch, conditio	nal branch, conditio	nal execution	, and functio	n calls), Mul	tiply accumulate
(MAC) instruction	ons, Divide instruc	tions, Memor	ry barrier in	structions, E	Exception-related
instructions, Slee	ep mode-related ins	tructions, Oth	ner functions	, Introductio	on to Cortex-M4
processor suppor	rt for Enhanced D	SP instructio	ns, Writing	C and Ass	embly language

Course Outcome: After successful completion of this course students will be able to

CO 1	Explain the Basic knowledge of interfacing with
	Embedded System.
CO 2	Analyse the process design of embedded system.
CO 3	Realize the architecture of PIC 16F Microcontroller
	Series.
CO 4	Familiar with the fundamentals of ARM Processor
	Cortex M3 & M4.
CO 5	Apply the knowledge of ARM Instruction Set for
	programming.

Text books

programs.

- 1. Introduction to Embedded Systems, A Cyber physical approach, Edward A. Lee and Senjit A. Seshia.
- 2. Embedded Systems Design: An Introduction to Processes, Tools, and Techniques, by Arnold S. Berger, CMP Books.

Reference Books

- **1.** Designing Embedded Systems with PIC Microcontrollers: Principles and Applications, 2nd Edition, Tim Wilmshurst, Elsevier Publication.
 - 2. PIC Microcontroller and Embedded Systems Using Assembly and C for PIC 18 by Muhammad Ali Mazidi, Rolin D. McKinlay and Danny Causey, Pearson Publication.
 - **3.** The Definitive Guide to ARM Cortex M3 and Cortex-M4 Processors, Third Edition, Joseph Yiu, Elsevier Publication, 2015.
- 4. ARM Assembly Language Fundamentals and Techniques, William Hohl and Christopher Hinds, CRC Press, 2015.

	M. TECH FIRST YEAR				
Course Code	AMTVL0218 L T	Р	Credit		
Course Title	Real Time Operating System3 0		03		
Course Object		•			
1	To provide the concept of real time operating system.				
2	To analyse the task scheduling method & I/O system.				
3	To realize the firmware design process.				
4	To familiar with the different types of management system				
5	for RTOS. To explain the concept of RTX.				
-	Digital System design, Microcontroller.				
TTC TCquisites.	Course Contents / Syllabus				
	OPEN SOURCE RTOS		8 hours		
UNIT-I			8 hours		
	Real-time concepts, Hard Real time and Soft Real-time				
	Purpose OS & RTOS, Basic architecture of an RTOS, Sched				
Inter-process cor	nmunication, Performance Matric in scheduling mod	els,	Interrupt		
management in F	RTOS environment, Memory management, File systems,	I/O	Systems,		
Advantage and di	sadvantage of RTOS. POSIX standards, RTOS Issues - Se	lect	ing a Real		
-	ystem, RTOS comparative study. Converting a normal Linux		-		
	mai basics. Overview of Open source RTOS for Embedded				
		5y5			
	T) and application development		0.1		
UNIT-II	Vx WORKS/ FREE RTOS		8 hours		
	TOS Scheduling and Task Management – Real time scheduli	<u> </u>			
Creation, Intertask	Communication, Pipes, Semaphore, Message Queue, Signal	ls, S	ockets,		
Interrupts. I/O Sys	stems – General Architecture, Device Driver Studies, Driver	Mod	lule		
explanation. Imple	ementation of Device Driver for a peripheral.				
UNIT-III	EMBEDDED FIRMWARE DESIGN AND		10 hours		
0111-111	DEVELOPMENT				
Embedded Firmw	are Design Approaches, Super-loopbased approach, Embed	ded	Operating		
• • • •	roach, Programming in Embedded C, Integrated developmer	n en	whomment		
× /:	of IDEs for Embedded System Development.				
UNIT-IV	EMBEDDED SYSTEM DESIGN WITH FREE RTOS		6 hours		
Queue Manageme	ent, Characteristics of a Queue, Working with Large I)ata	, Interrupt		
Management, Que	eues within an Interrupt Service Routine, Critical Sections and	nd S	uspending		
6	source Management, Memory Management.		1 0		
UNIT-V	RTX		8 hours		
	TX files, RTX task and time management, Simple Time Man				
•	heme in RTX, Inter-Task Communication, Event, Inte	-			
C 1		1 '			
- ·	boxes and Messages in RTX, RTX control functions, A	rch	itecture of		
Semaphore, Maill CMSIS-RTOS.	boxes and Messages in RTX, RTX control functions, A	rch	tecture of		
CMSIS-RTOS.	boxes and Messages in RTX, RTX control functions, A ne: After successful completion of this course students w				

CO 2	Analyse the task scheduling method & I/O system.	
CO 3	Realize the firmware design process.	
CO 4	Familiar with the different types of management system for	
	RTOS.	
CO 5	Explain the concept of RTX.	
Text books		
1. Venka	ateswaranSreekrishnan,"Essential Linux Device Drivers", Ist Kind	lle edition,
Prenti	ce Hall, 2008	
2. Jonath	nan W. Valvano, "Real-Time Operating Systems for ARM	Cortex-M
Micro	controllers" Jonathan Valvano; 4 edition	
Reference	Books	
1. Jerry	Cooperstein, "Writing Linux Device Drivers: A Guide with Exe	ercises", J.
Coope	erstein publishers ,2009	
2. Qing	Li and Carolyn Yao,"Real Time Concepts for Embedded Systems"	– Qing Li,
Elsevi	er ISBN:1578201241 CMP Books © 2003	-
2 "TT."	$4 + E_{\text{max}} + DTOC D = 1 T'_{\text{max}} + V = 12 E_{\text{max}} + DTOC$	

- "Using the FreeRTOS Real Time Kernel" From Free RTOS.
 Sam Siewert, "Real-Time Embedded Systems And Components".

	M. TECH FIRST YEAR		
Course Code	AMTVL0219	LT P	Credit
Course Title	System On Chip (SOC) Design using ARM	300	03
Course Object	ive:		
1	Study the Architecture of Arm Cortex-M0 Processor.		
2	Describe the AMBA 3 AHB-Lite Bus Architectur	e,	
	VGA, GPIO and 7-Segment UART Peripheral		
3	Learn the Programming of SoC Using C Language.		
4	Compare ARM Cortex-A9 Processor with other		
	processor.		
5	Implement and compare an AXI UART and AXI- Stream Peripheral		
Dro roquisitos	1. Basics of HDL (Verilog /VHDL)		
	2. Basics of Microcontroller Assembley language Progr	ramming	Ţ
	Course Contents / Syllabus	amming	>
UNIT-I	INTRODUCTION TO SYSTEM-ON-CHIP	8	3 hours
	DESIGN		
Differences amon	g SoCs, CPUs and MCUs, Arm Cortex-M0 Processor A	rchitect	ure.
UNIT-II	PROGRAMMING AN SOC		8 hours
AMBA 3 AHB-I	Lite Bus Architecture, AHB VGA Peripheral, AHB	UART	Peripheral,
	d 7-Segment Peripherals, Interrupt Mechanisms, Pro	grammi	ng an SoC
Using C Language			
UNIT-III	ARM CORTEX-A9 PROCESSOR		8 hours
Arm CMSIS and ARM Cortex-A9	Software Drivers, Arm Development Studio, ARMv7-	A/R ISA	Overview,
	AMBA AXI4		0 h a u wa
UNIT-IV			8 hours
	us Architecture, Design and Implementation of an ADDR Memory Controller	AX14-L1	te ^{rm} GPIO
UNIT-V	IMPLEMENTATION OF AN AXI UART AND		8 hours
	AXI-STREAM		0 nours
U 1	mentation of an AXI UART and AXI-Stream Periphera	l, AXI4-	Stream and
VGA Peripheral,	HDMI Input Peripheral, System Debugging.		
Course Outcon	me:After completion of this course students will be a	uble to	
CO 1	Explain Arm Cortex-M0 Processor Architecture.		
CO 2	RecognizeAMBA 3 AHB-Lite Bus Architectur	e,	
	VGA, GPIO and 7-Segment UART Peripheral.		
CO 3	Program SoC Using C Language.		
CO 4	Explain ARM Cortex-A9 Processor.		
CO 5	Design and Implement an AXI UART and AXI-		
	Stream Peripheral.		
Text books			

- 1. ARM System-on-Chip Architecture by Steve B. Furber
- 2. ARM Assembly Language: Fundamentals and Techniques by William Hohl
- 3. The Definitive Guide to the ARM Cortex-M0 by Joseph Yiu

Reference Books

- 1. Computer System Design: System-On-Chip Michael J. Flynn and Wayne Luk, Wiely India.
- 2. Modern VLSI Design System on Chip Design Wayne Wolf, Prentice Hall,
- 3. Design of System on a Chip: Devices and Components, Ricardo Reis, Springer
- 4. System on Chip Verification Methodologies and Techniques: Prakash Rashinkar, Peter Paterson and Leena Singh L, Kluwer Academic Publishers

Link:	
Unit 1	https://www.youtube.com/watch?v=PRQXzjTrCJY
II '4 0	https://www.youtube.com/watch?v=HNbeVvfFKsQ
Unit 2	https://www.youtube.com/watch?v=j2NI4AXRs1Uhttps://www.youtube.com/watch?v= 4VRtujwa_b8&list=PL90187D2B8F5AC28F&index=5
Unit 3	https://www.youtube.com/watch?v=4VRtujwa_b8
Unit 4	https://www.youtube.com/watch?v=mYP5SxDEjrM
	https://www.youtube.com/watch?v=QQY-h0HGHnI
	https://www.youtube.com/watch?v=tEvtb-
	mdJ4s&list=PL90187D2B8F5AC28F&index=16
Unit 5	https://www.youtube.com/watch?v=nbWWMPPC8aE
	https://www.youtube.com/watch?v=MANrmky5DfE